## Notice of References Cited Application/Control No. 09/674,660 Examiner Alexis Wachtel Applicant(s)/Patent Under Reexamination BHARDWAJ ET AL. Page 1 of 1

## **U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-6841141	01-2005	Arno et al	423/490
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